



SW Test Workshop

Semiconductor Wafer Test Workshop

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AP to LPDDR Probe Card



Jung Keun Park

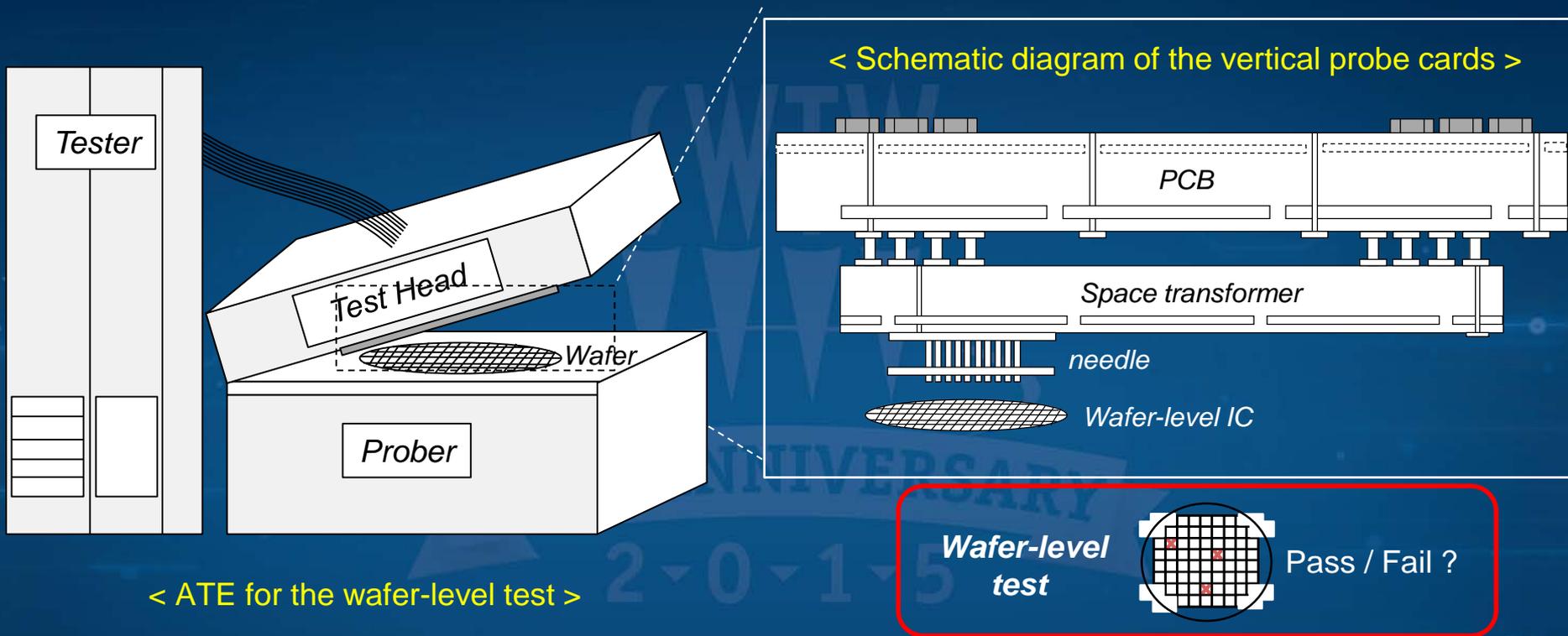
Jennifer Lee

Will Technology

Overview

- Introduction
- Probe Card Architecture
- SI / PI Simulation
- Measurement
- Conclusion

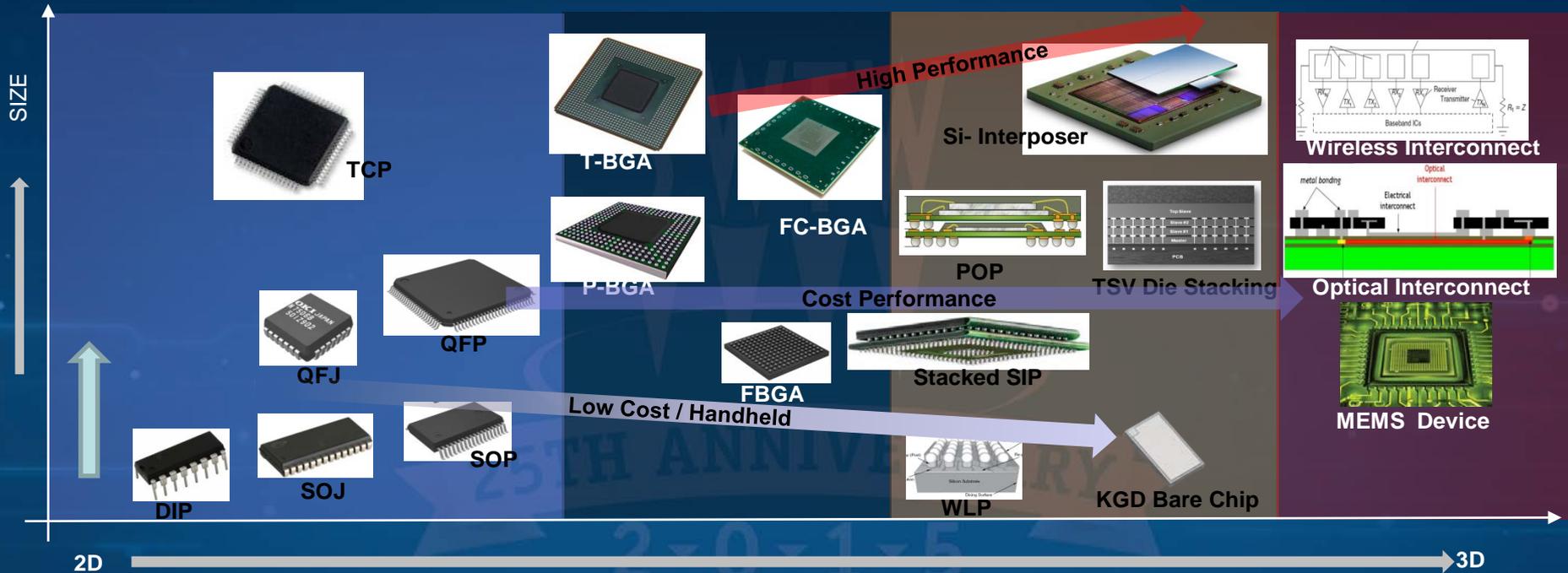
Introduction



< ATE for the wafer-level test >

- Decrease the overall cost of testing by detecting chip fail before packaging .
- As the quality of the probe card has a strong influence on the IC yield, high reliability on the probe card is required in the wafer test process.

Introduction



- 3D structure of TSV or POP is generally applied for the Package Types.
- When problem occurs between package to package on POP structure,

→ **Will Technology proposes a probe card structure that will eliminate unnecessary cost and time that may occur at package level through increasing test credibility at the Wafer Level.**

Introduction

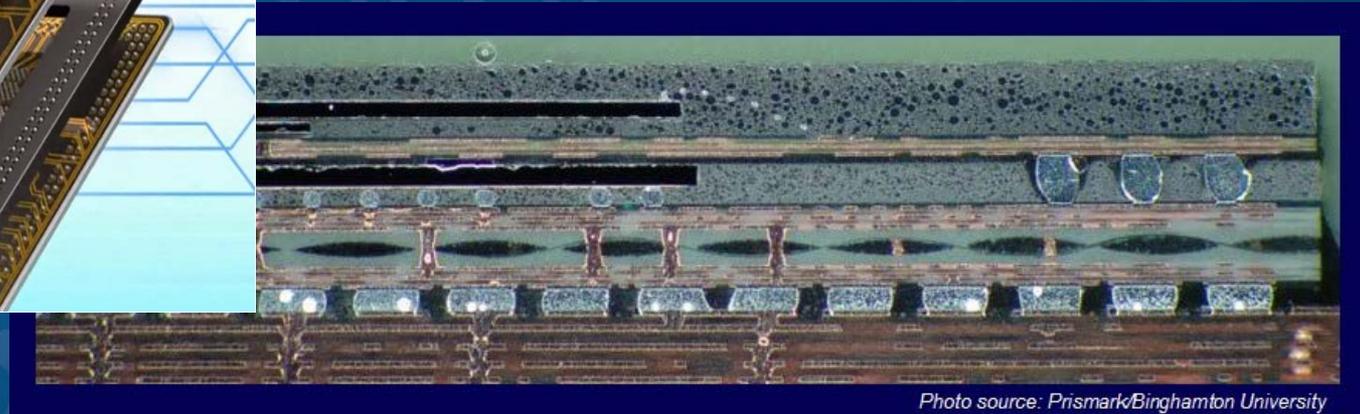
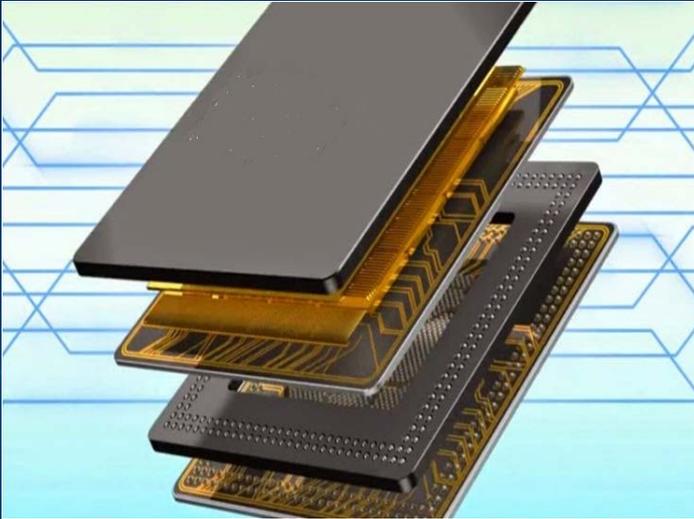
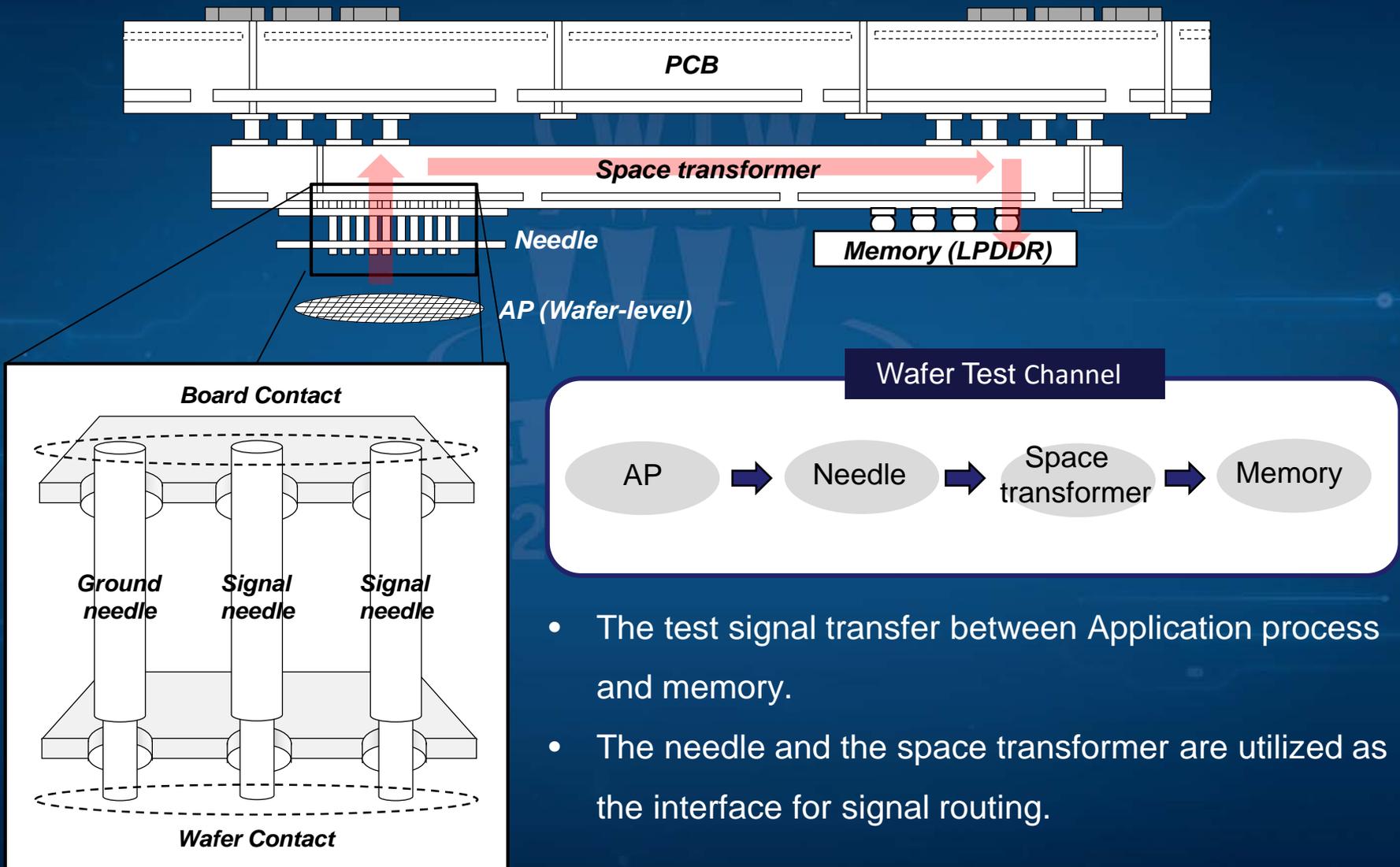


Photo source: Prismark/Binghamton University

- **Development Plan**

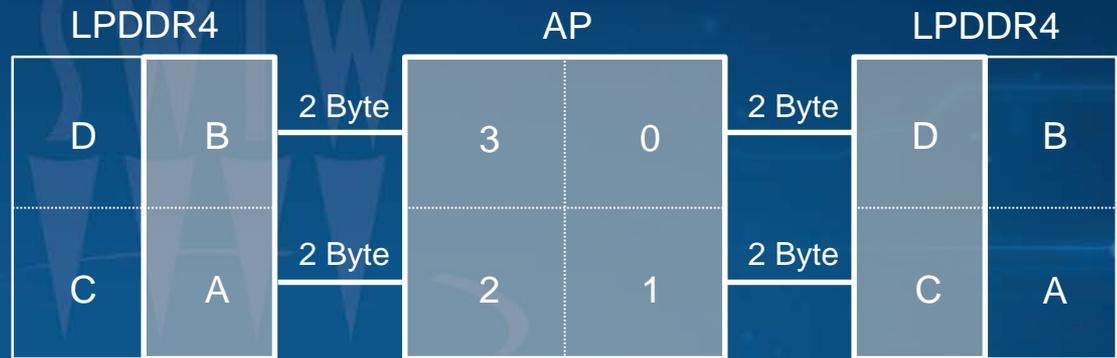
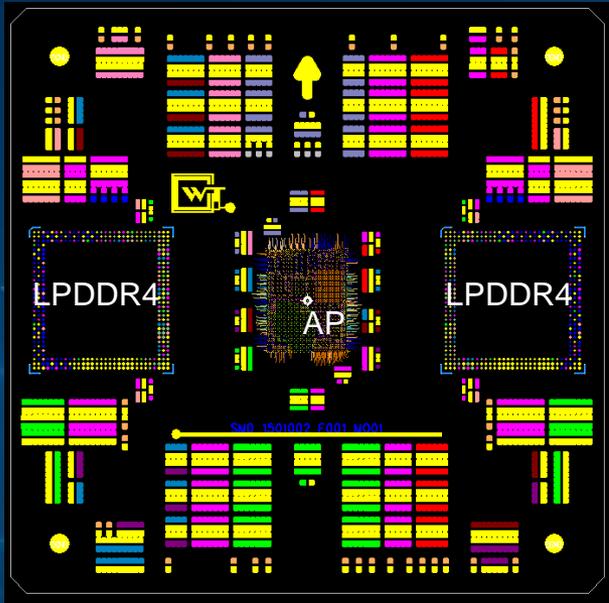
- Current: Unable to test AP & Memory at Wafer Level
- AP & Memory is tested at Package on Package
- Extra cost occurrence from untested AP & Memory
- High Speed performing Probe Card development need for AP & Memory

Probe Card Architecture



- The test signal transfer between Application process and memory.
- The needle and the space transformer are utilized as the interface for signal routing.

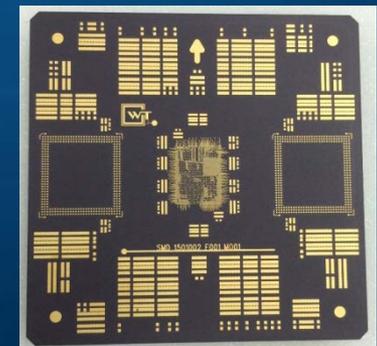
MLC Design



2 Byte x 4 Channel = 8 Byte

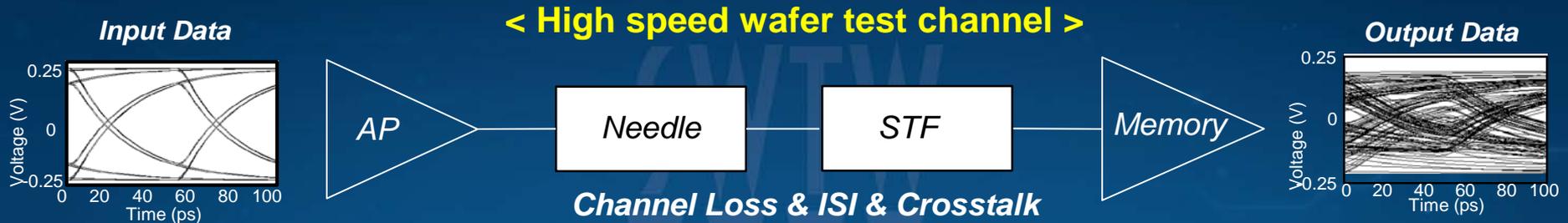
- **MLC Design**

- Place LPDDR on Left/Right of AP for shorter path between AP-LPDDR
- Short Routing Length

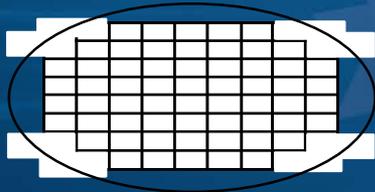


<MLC>

Simulation Condition



- Increasing pad density
- Narrowing pad pitch



AP (Wafer-level)

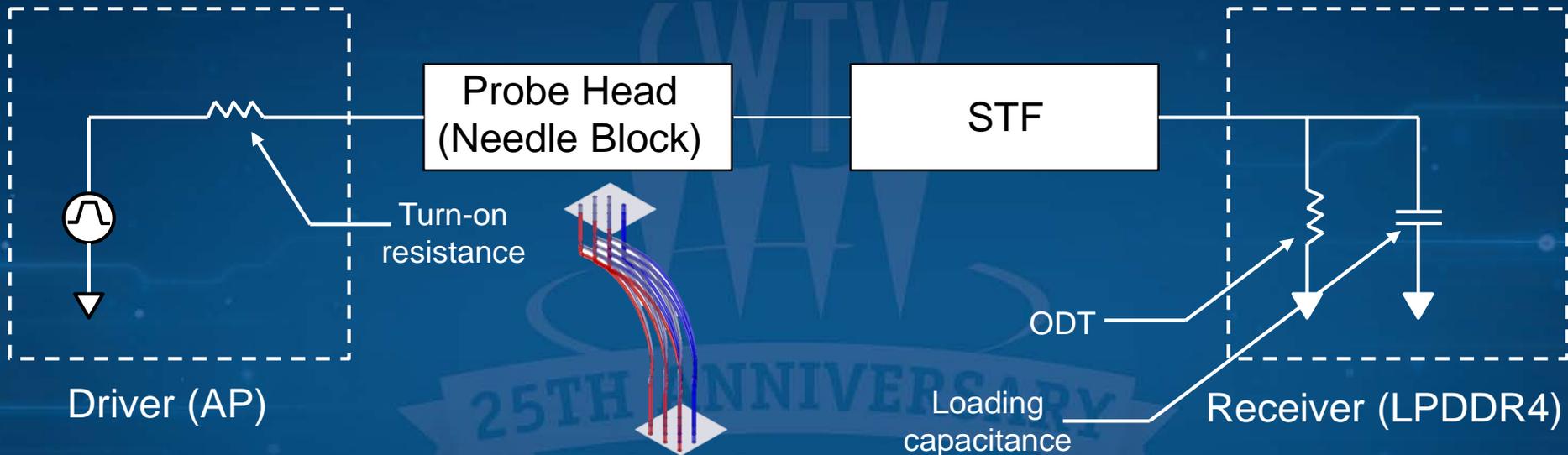
		LPDDR3	LPDDR4
Perform	B/W	12.8GB/s	25.6GB/s
	Data rate	1.6Gbps	3.2Gbps
number of IO		x64	X64

<LPDDR target electrical specification>

- Input data is degraded by channel loss, ISI and crosstalk in high-speed test channel
- To improve reliability of wafer test channel in probe card, it is necessary to analyze Signal integrity & Power Integrity

Simulation Condition

- SIMULATION CONDITION**



- Input Voltage: 1.1 V
- Data rate: DQ group → 1600 Mbps, 3200 Mbps, CA group → 800 Mbps, 1600 Mbps
- Rise / Fall Time: UI/4
- Turn-on resistance: 48 ohm
- Data pattern: PRBS 2^5
- Loading Capacitance: 2pF
- ODT: 48 ohm

Signal Integrity

- **Insertion Loss**

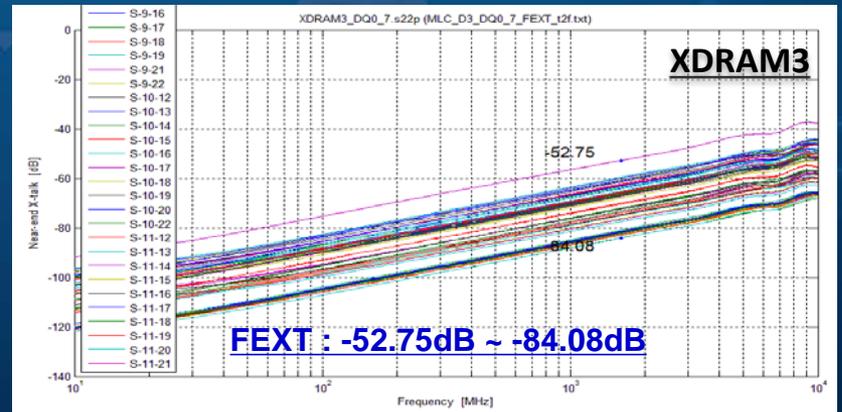
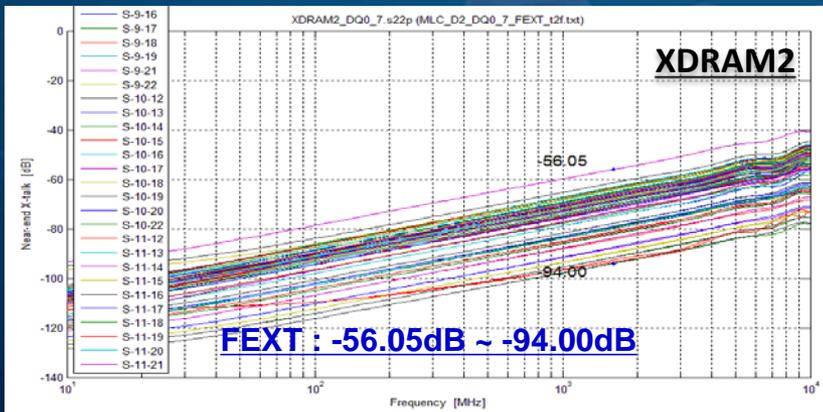
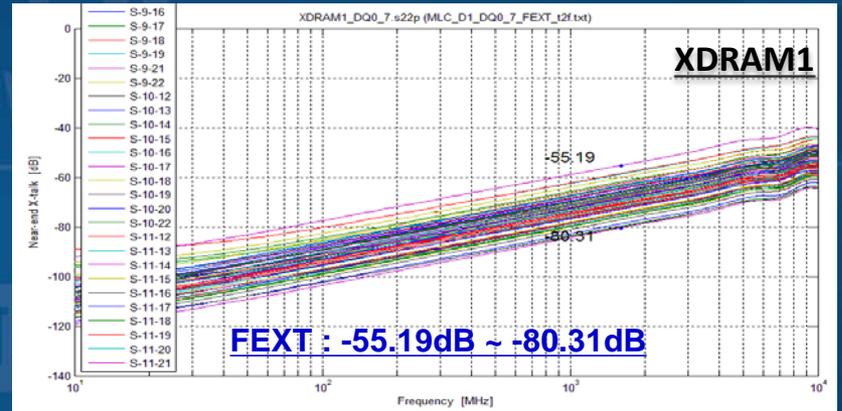
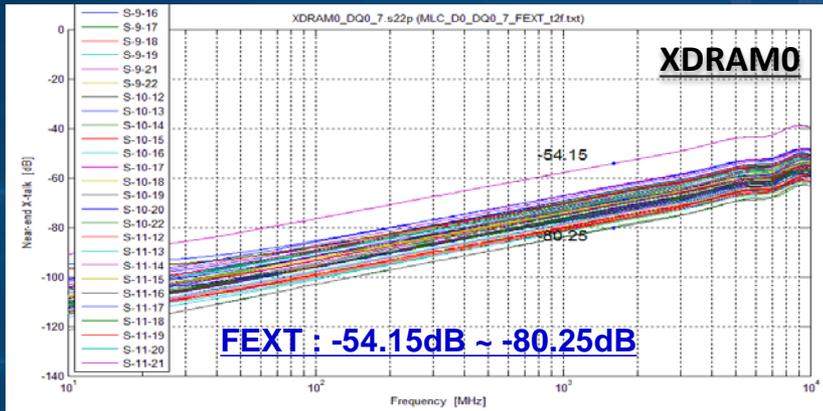
- DRAM Channel SI Simulation
- Low Insertion Loss (Approx. -0.6dB)



Signal Integrity

- **Crosstalk Noise**

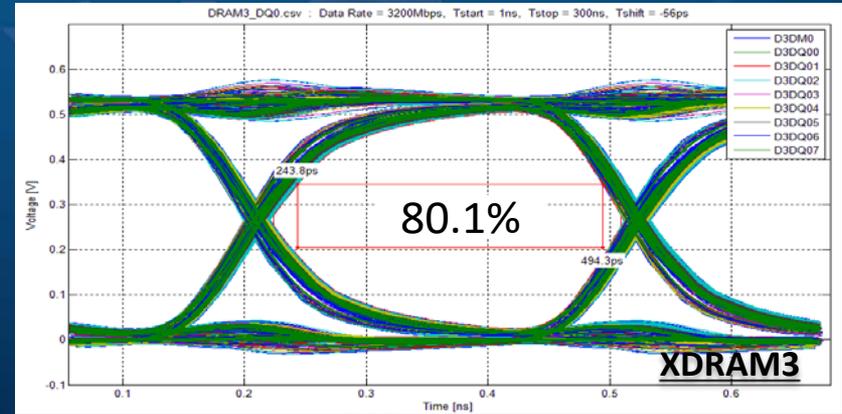
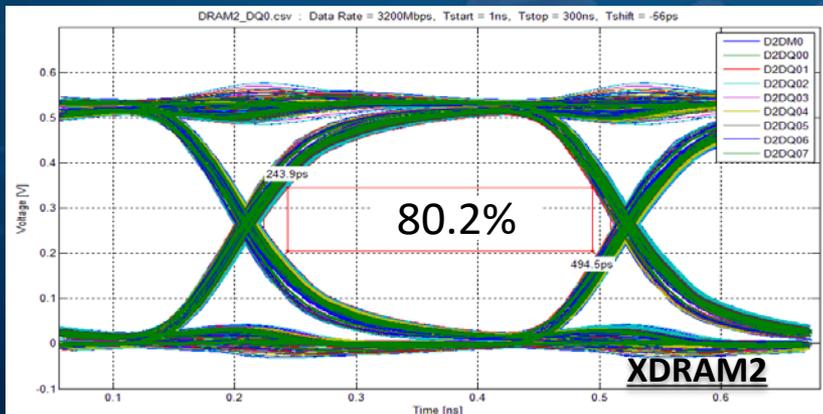
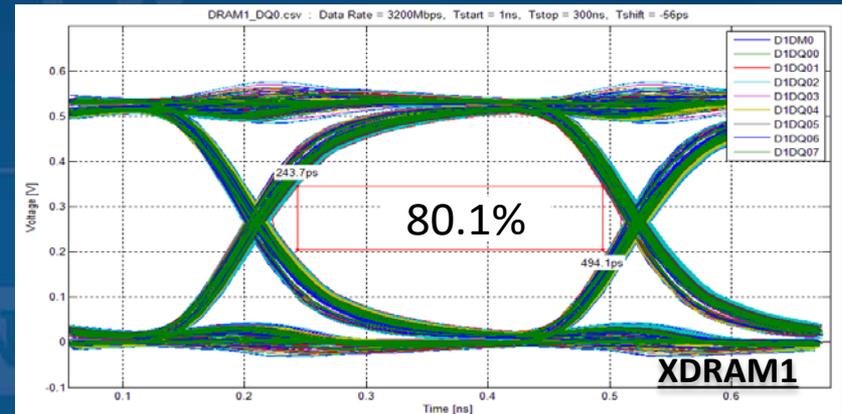
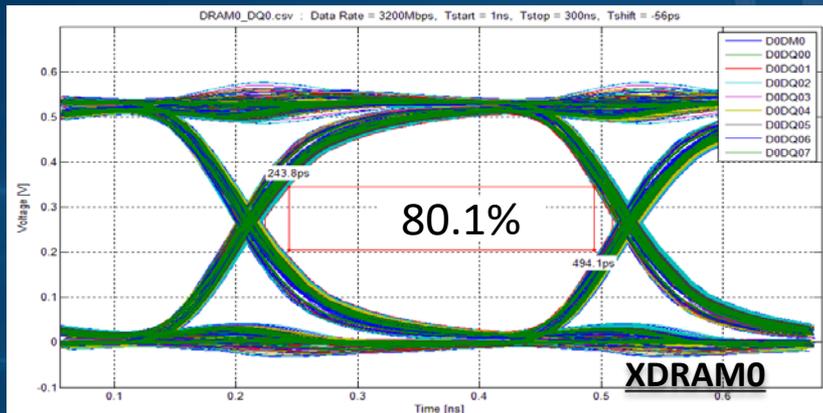
- DRAM Channel SI Simulation
- Low Crosstalk Noise (Approx -52dB ~ -90dB)



Signal Integrity

- **Eye Diagram**

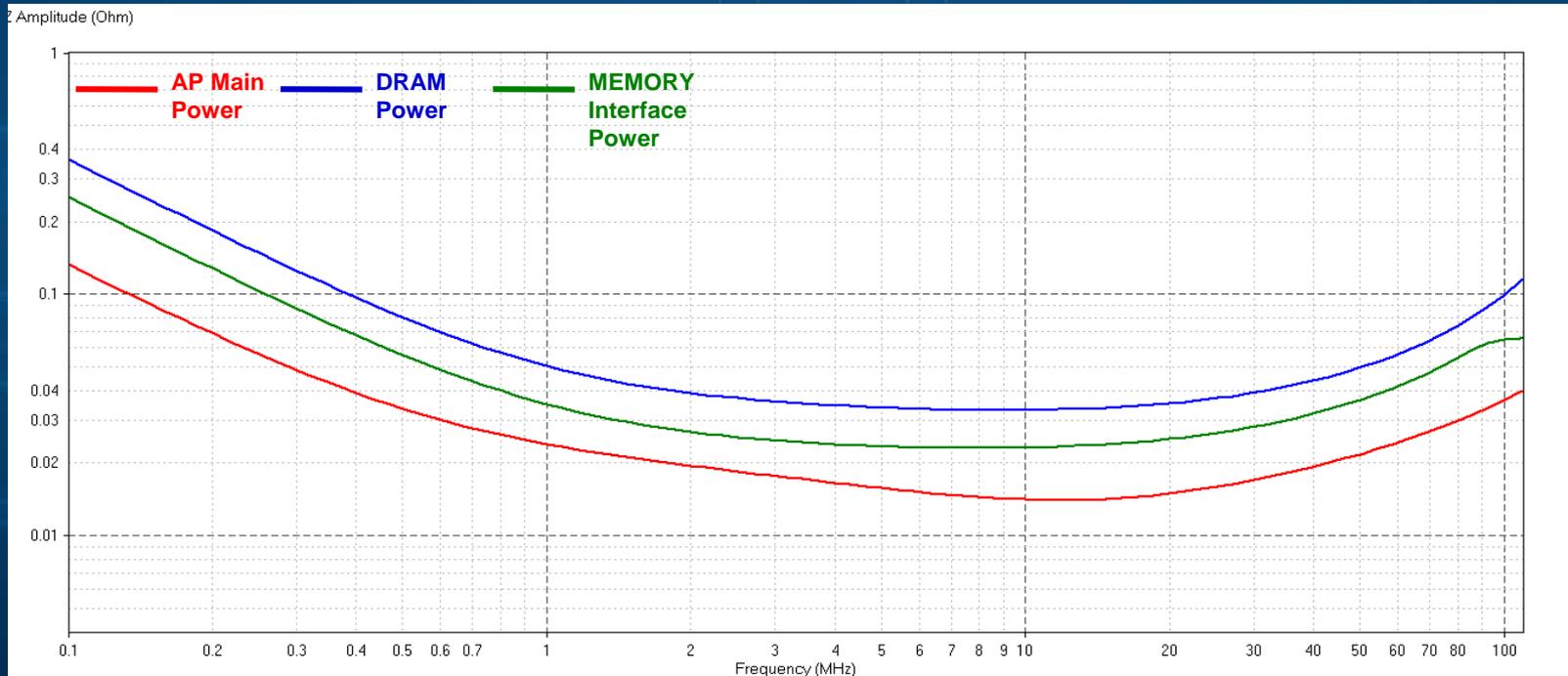
- DRAM Channel Eye Simulation (@3.2Gbps)
- Eye Opening : Approx. 80%



Power Integrity

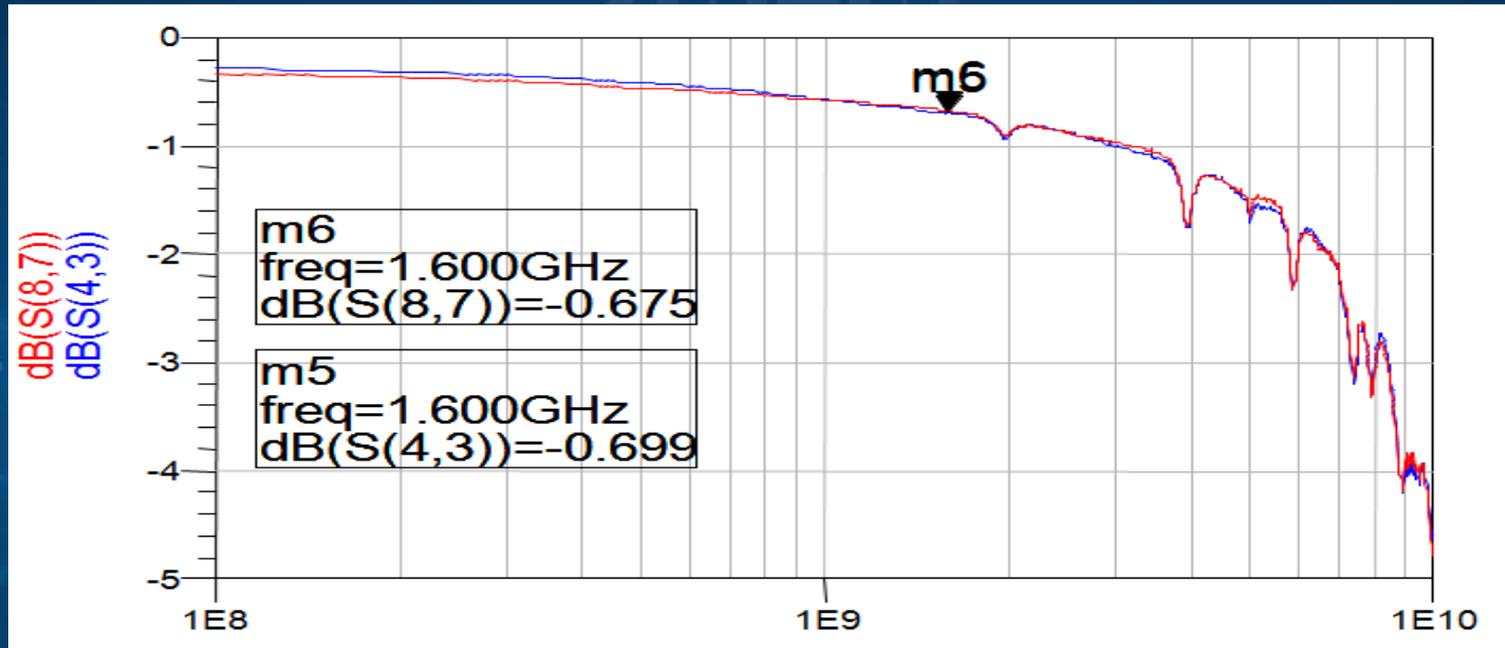
- **Power Impedance**

- PI designs for Low Z implementation
- Design based on prioritizing Power / AP Main Power related to Memory



Measurement

- SI Measurement (Insertion Loss)

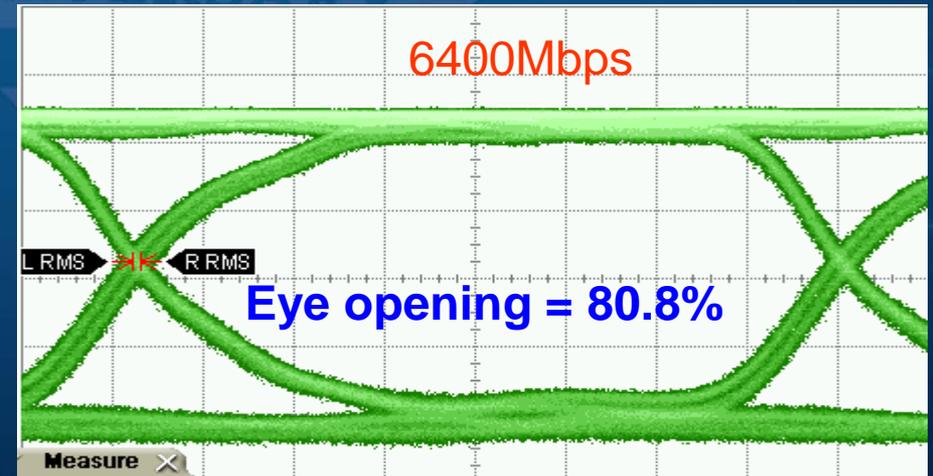
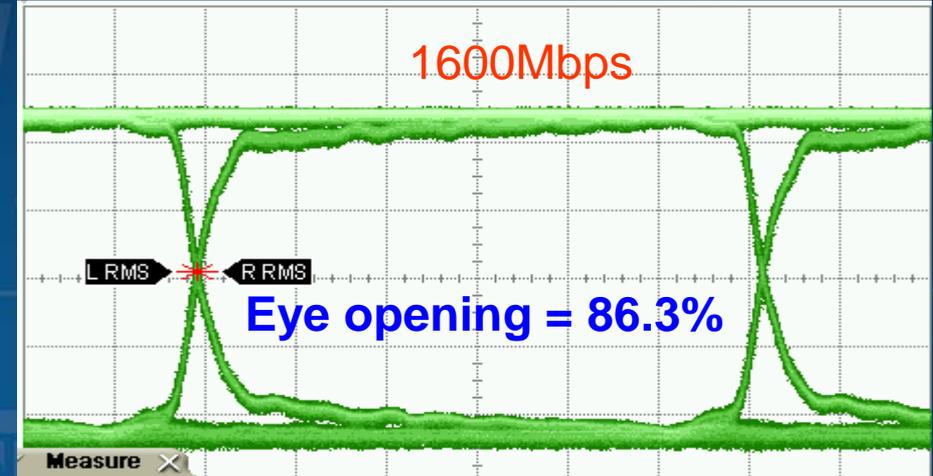
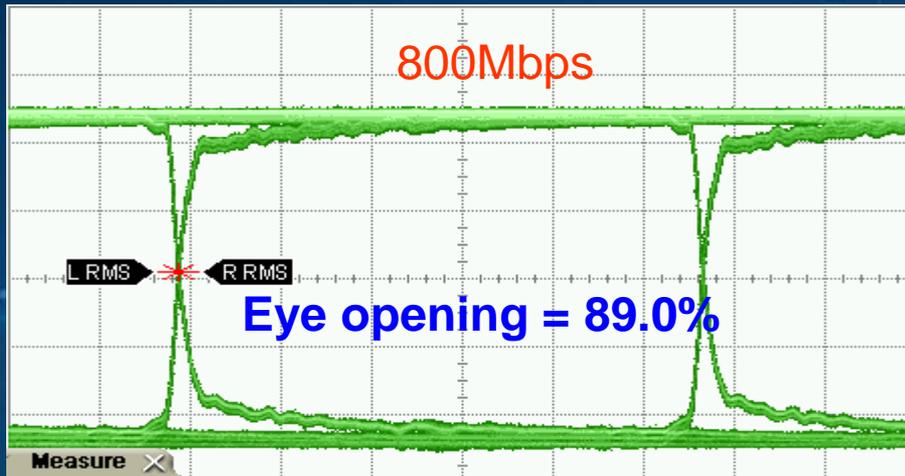


Insertion Loss Measurement

- Measure Insertion Loss (S_{21}) similar to simulation result
- Confirm low Insertion Loss through actual measurement

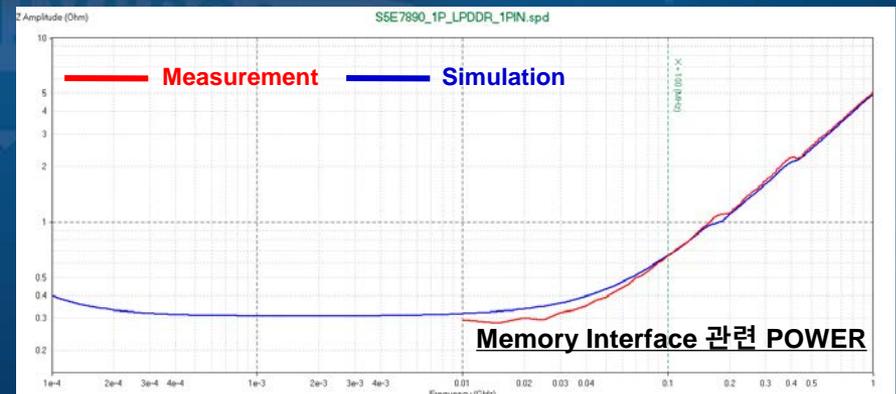
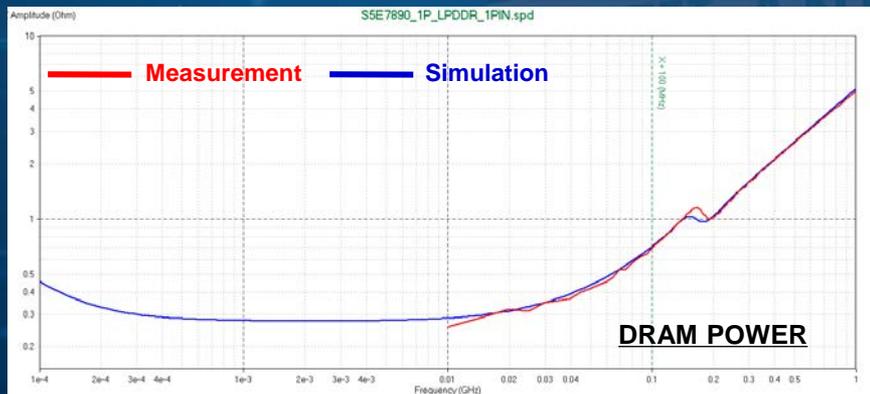
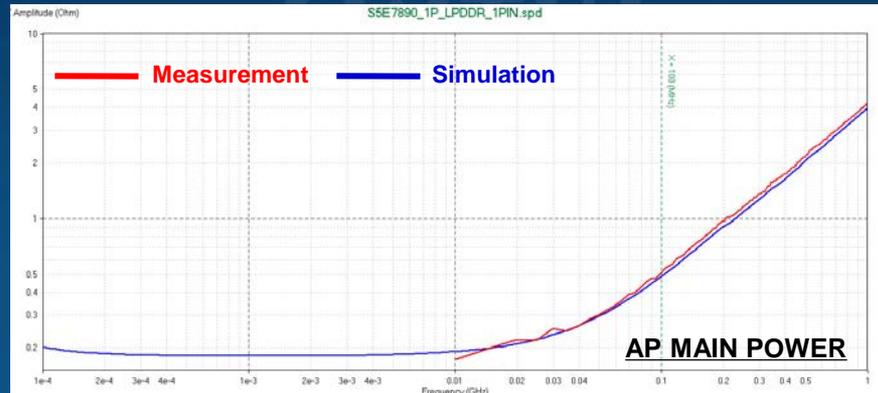
Measurement

- SI Measurement (Eye Diagram)



Measurement

- PI Measurement (1Pin Power Impedance)

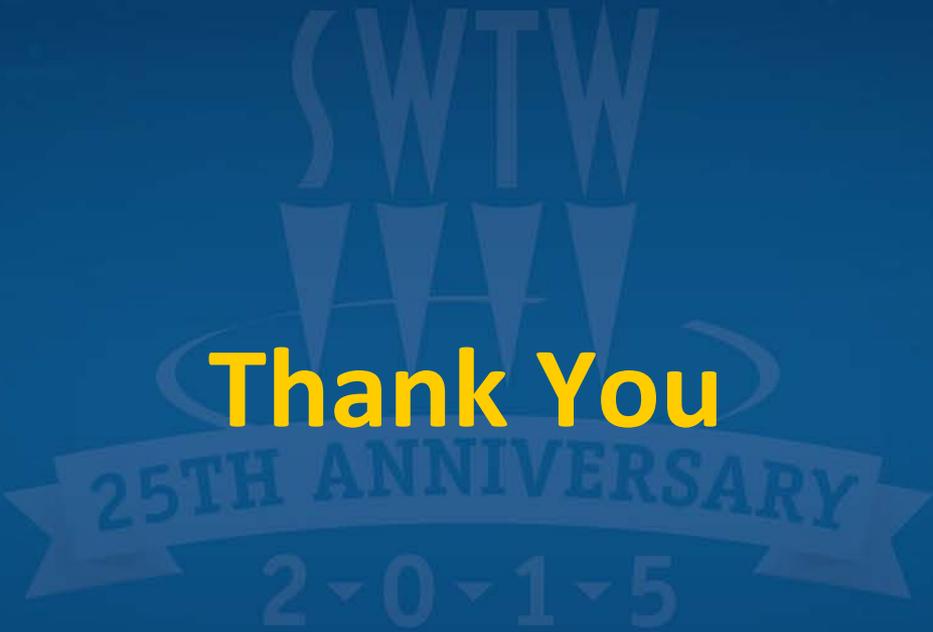


Confirm Power Impedance through Simulation & Measurement Correlation

Conclusions & Future Works

Expected Benefits

- Yield increase through AP-Memory Channel Test at wafer level before Packaging
- High Speed Test (Able Testing at Actual Operating Speed)
- Target :
Production of Probe Card capable of performing at 3.2Gbps or faster



Thank You